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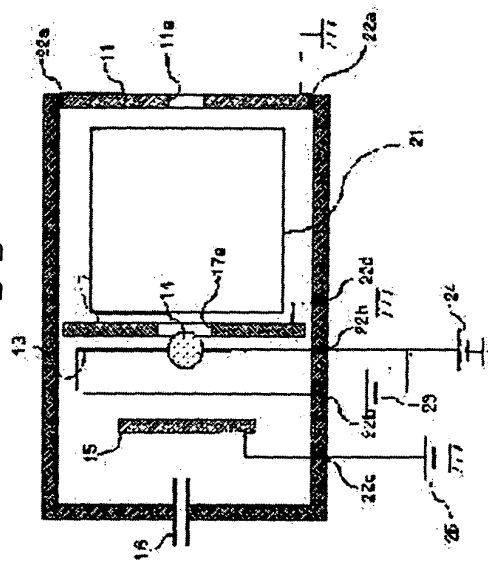
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(54) ION SOURCE FOR ION ATTACHED MASS SPECTROMETER

(57)Abstract:

PROBLEM TO BE SOLVED: To provide an ion source for an ion attached mass spectrometer capable of forming a sufficient quantity of detected gas ion in mass spectrometry to feed it to the outside of the ion source by preventing the formation of space charge in the ion source.

SOLUTION: This ion source is provided with a gas lead-in part 16 for leading detected gas into an internal space, an emission body 14 for generating metal ion by the feed of a voltage applying part 13, and a first aperture 11 with an aperture 11a. The metal ion is attached to the detected gas to generate the detected gas ion, and the detected gas ion is fed to an external mass spectrometric mechanism through the aperture 11a. Further, an electrode is disposed either near the emission body or near the aperture 11a of the first aperture 11.



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